

	Type	L #	Hits	Search Text
1	BRS	L1	655063	(clean or cleaning or cleaned or cleaner or cleanse or cleansing or cleansed or cleanser or strip or stripping or stripped or stripper or treat or treating or treated or treatment or etch or etching or etched or etchant or decontaminate or decontaminating or decontaminated or decontamination or degrease or degreasing or degreased or degreaser) with (semiconductor or wafer or silicon or electronic or workpiece or work-piece or substrate)
2	BRS	L2	4798	(surfynol\$ or dynol\$ or "SURFYNOL" or "DYNOL" or "SURFYNOL.RTM" or "DYNOL.RTM" or acetylen\$3 adj3 diol)
3	BRS	L3	2756	air adj3 products adj2 chemical\$.asn.
4	BRS	L4	968	zhang-p\$.in.
5	BRS	L5	603	ross-b\$.in.
6	BRS	L6	1081	11 and 12

	DBs	Time Stamp	Comments	Error Definition
1	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2006/02/02 08:04		
2	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2006/02/02 08:05		
3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2006/02/02 08:06		
4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2006/02/02 08:06		
5	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2006/02/02 08:06		
6	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2006/02/02 08:07		

	Type	L #	Hits	Search Text
7	BRS	L7	56	l1 same l2
8	BRS	L8	124	(l6 or l7) and (CMP or chemical adj3 mechanical adj3 polishing or chemical adj3 mechanical adj3 planarization or post-CMP or post adj CMP)
9	BRS	L9	51501	("134"/\$).ccls.
10	BRS	L10	11	l8 and l9
11	BRS	L11	4314	l4 or l5 or l3
12	BRS	L12	23	l11 and l1 and l2